

A beamer tutorial

*LayoutBeamer*, from GenISys GmbH

Beamer, or “LayoutBeamer” is a program which converts pattern shapes to machine-specific formats, chopping polygons into trapezoids, and cutting large patterns at exposure field boundaries. Patterns will be stitched together by writing each field, then moving the stage.

Many e-beam systems and mask writers can use the same pattern fracturing software, and so a company such as GeniSys can provide better support with a broader customer base than Vistec et al.

The main competitor is “Cats” from Synopsys, which has been the defacto standard (until recently), and is used on many e-beam writers. Cats is very mature and bug-free, but also very expensive.



```
rooks@lardnar:~/projects/cat
File Edit View Terminal Tabs Help

[rooks@lardnar cat]$ beamer

Before starting Beamer, I need to ask your name and phone number.
That way, if you forget to stop Beamer then the next user can be
polite and considerate about taking control of the program.

Please enter your name > Mike

Please enter your phone number > 2034324559

Starting LayoutBEAMER...

█
```

new flow - Layout BEAMER

File Edit View Help

Cut Copy Paste Up Save Run Run To Cancel Reset Viewer Detach

Base Modules Central Flows User Flows

Layout Operation

Import Edit

Export

Extract Filter Transform

Grid

Heal NOT Bias

P-XOR Merge

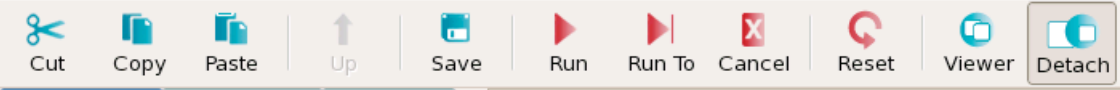
OR AND MINUS

XOR

Process Correction

REC Shape REC 3D REC

Module Info Log Info

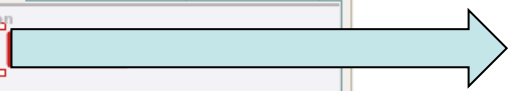


Base Modules Central Flows User Flows

Layout Operation

Import Export Extract Filter Transform Grid Heal NOT Bias P-XOR Merge OR AND MINUS XOR

Import



Open File

rooks projects cat

Places	Name	Modified
rooks	bricks_line.gds	08/31/2010
Desktop	circles.gds	Today
File System	foo.gds	Today
	resist.gds	12/12/2010
	rings.gds	10/10/2010
	yale_cat_2.gds	Yesterday

+ Add - Remove GDS files (\*.gds) Cancel Open

Module Info

Process Correction

PEC Shape-PEC 3D-PEC FDA

Verification

E-Beam Metrology

Control

Split Loop Script Optimizer



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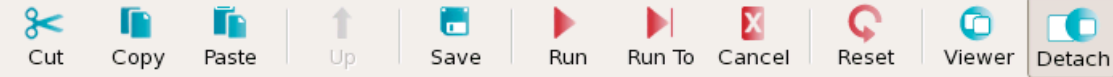
Loop Script Optimizer



click on the "play" button so that the next module will see all the available cells.

Module Info Log Info

```
Import ./foo.gds
File type: GDSII file
Layerset: *
Single Path Import OFF
Boxes Import OFF
Zero Path Width 0.000000
```



Base Modules Central Flows User Flows

Layout Operation

Buttons for layout operations: Import, Edit, Export, Extract, Grid, Heal, NOT, Bias, P-XOR, Merge, OR, AND, MINUS, XOR.



Buttons for 'Import' and 'Extract' in the main workspace.

Drag "extract" over on top of "import".

Select the top level cell.

Module Info Log Info

Geometry Compaction Factor: 1.0  
Cell Compaction Factor: 1.0  
Hierarchy Compaction Factor: 1.0  
Hierarchy Tree Depth: 1  
Area (in um2): 9.8364855124e+04  
Bbox (in um) : (-0.055, -0.079), (750...  
Coverage : 17.5 %  
CPU time: 0.8 seconds, Elapsed time:  
Memory usage: 94.500 MB additional,  
Read GDSII completed on Sat Jan 15 13

Extract dialog box with tabs for Extract and Extent. Fields include Layer(s) (\*), Extraction Type (Cell Extraction selected), Cell Name (--- entire layout ---), and a table for X Min, Y Min, X Max, Y Max in um. Buttons for Edit Layout, Delete Row, OK, Cancel, and Help are at the bottom.



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XOR

Process Correction

PEC Shape-PEC 3D-PEC

FDA

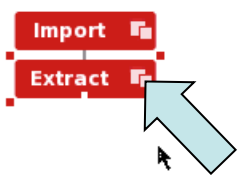
Verification

E-Beam Metrology

Control

Split

Loop Script Optimizer



click on the play button

Module Info Log Info

Geometry Compaction Factor: 1.0  
Cell Compaction Factor: 1.0  
Hierarchy Compaction Factor: 1.0

Hierarchy Tree Depth: 1

Area (in um2): 9.8364851024e+04  
Bbox (in um) : (249.875, 249.882), (750.125, 750.114)  
Coverage : 39.3 %

CPU time: 0.3 seconds, Elapsed time: 0.0 seconds  
Memory usage: 1024.000 kB additional, 85.496 MB total

Extract completed on Sat Jan 15 13:50:00 2011

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Base Modules Central Flows User Flows

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Drag "export" on top of "extract"

Save File

Name:

Save in folder:

Browse for other folders

Modu

Geo

Cell

Hierarchy Compaction Factor: 1.0

Hierarchy Tree Depth: 1

Area (in um2): 9.8364851024e+04

Bbox (in um) : (249.875, 249.882), (750.125, 750.114)

Coverage : 39.3 %

CPU time: 0.3 seconds, Elapsed time: 0.0 seconds

Memory usage: 1024.000 kB additional, 85.496 MB total

Extract completed on Sat Jan 15 13:50:00 2011

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Module Info Log Info

Geometry Compaction Factor: 1.0  
 Cell Compaction Factor: 1.0  
 Hierarchy Compaction Factor: 1.0  
 Hierarchy Tree Depth: 1  
 Area (in um2): 9.8364851024e+0  
 Bbox (in um) : (249.875, 249.882)  
 Coverage : 39.3 %  
 CPU time: 0.3 seconds, Elapsed ti  
 Memory usage: 1024.000 kB addi  
 Extract completed on Sat Jan 15 13:

Export EBPB

General Advanced Tool Extent

Format Type 5000+ wide field 20 bit 50 MHz

Writing Grid [um]

Resolution 0.005000000 Beam Step Size 0.005000000

Beam Step Size Fracturing

Optimize

None  File Size  Writing Speed

Diagonal Line Compression

Fracturing Mode

LRFT Large Rectangle Fine Trapezoid

Trapezoids

X and Y  X only

The default settings are almost always the best choices.

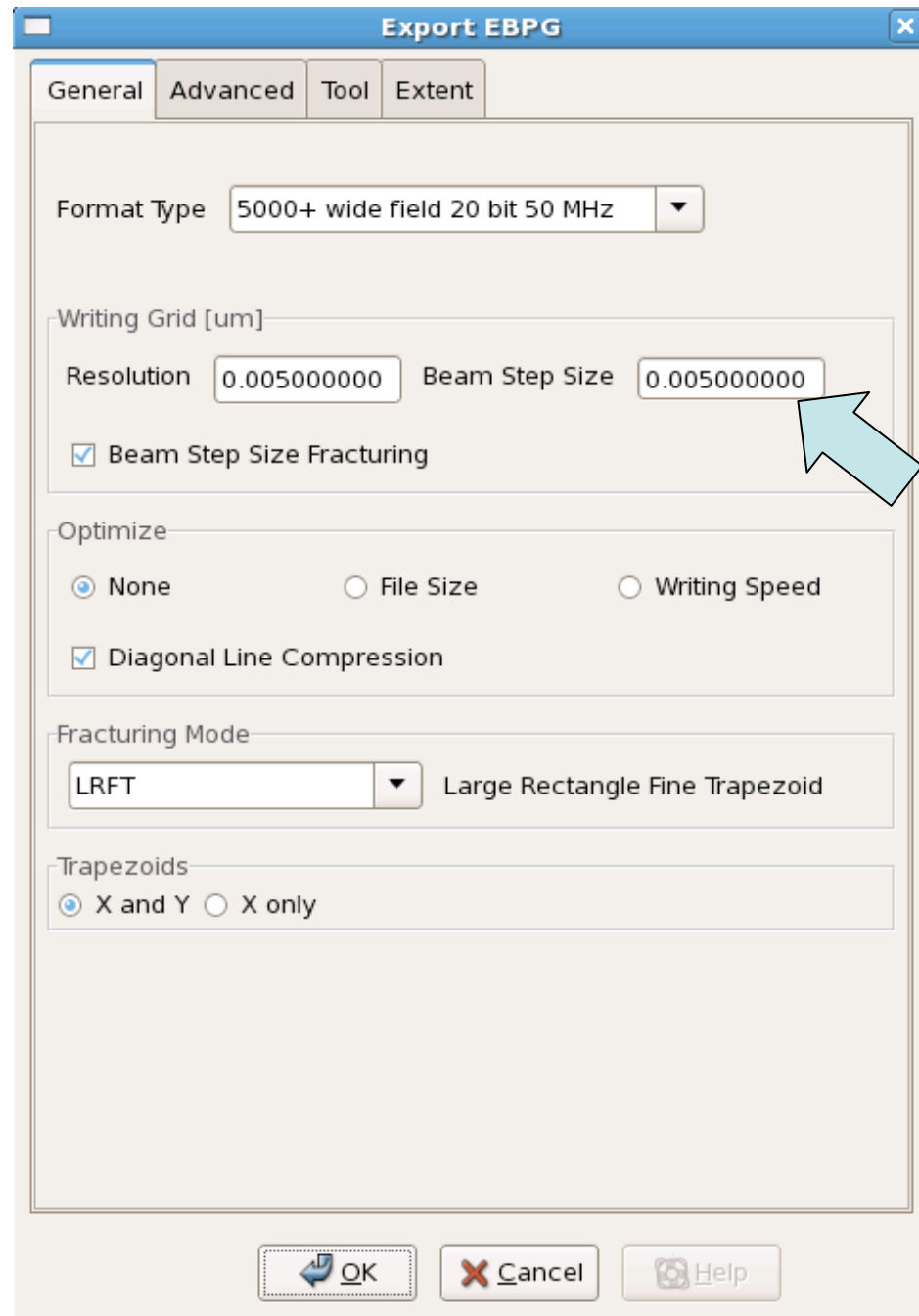
The two things you will have to choose: beam step size and field size.

In **this** dialog box, “resolution” means “fracturing resolution”. It should always equal the beam step size.

You should calculate the best beam step based on resist sensitivity and resolution requirements.

One way to do this is to use the EBPG calculator.

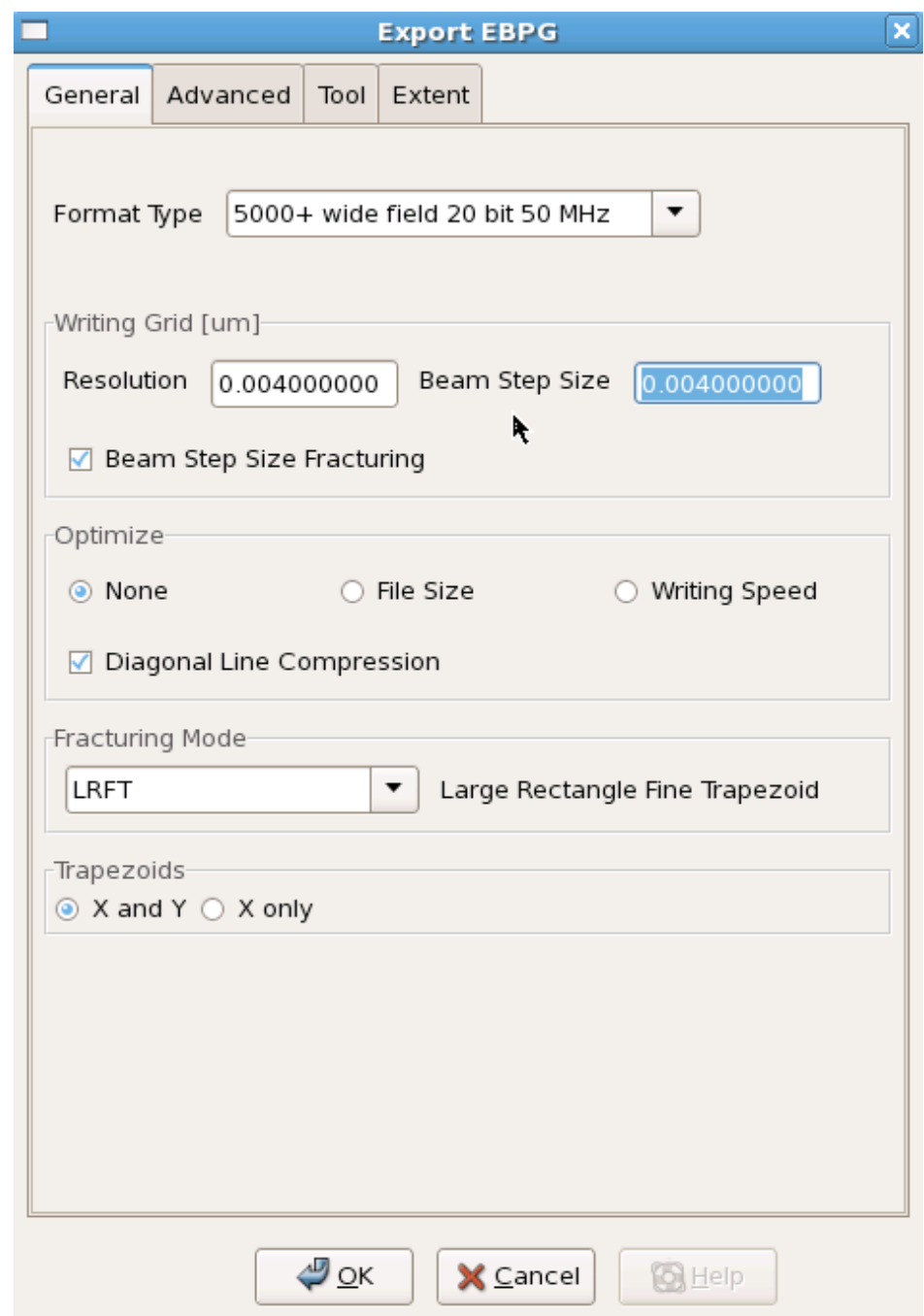
But really, you should have thought about the beam step long ago, before doing the CAD.



Let's change the beam step to 0.004 microns (4 nm).

Make sure the "resolution" is also 0.004 microns. It may or may not change by itself.

Next switch to the "Advanced" tab.



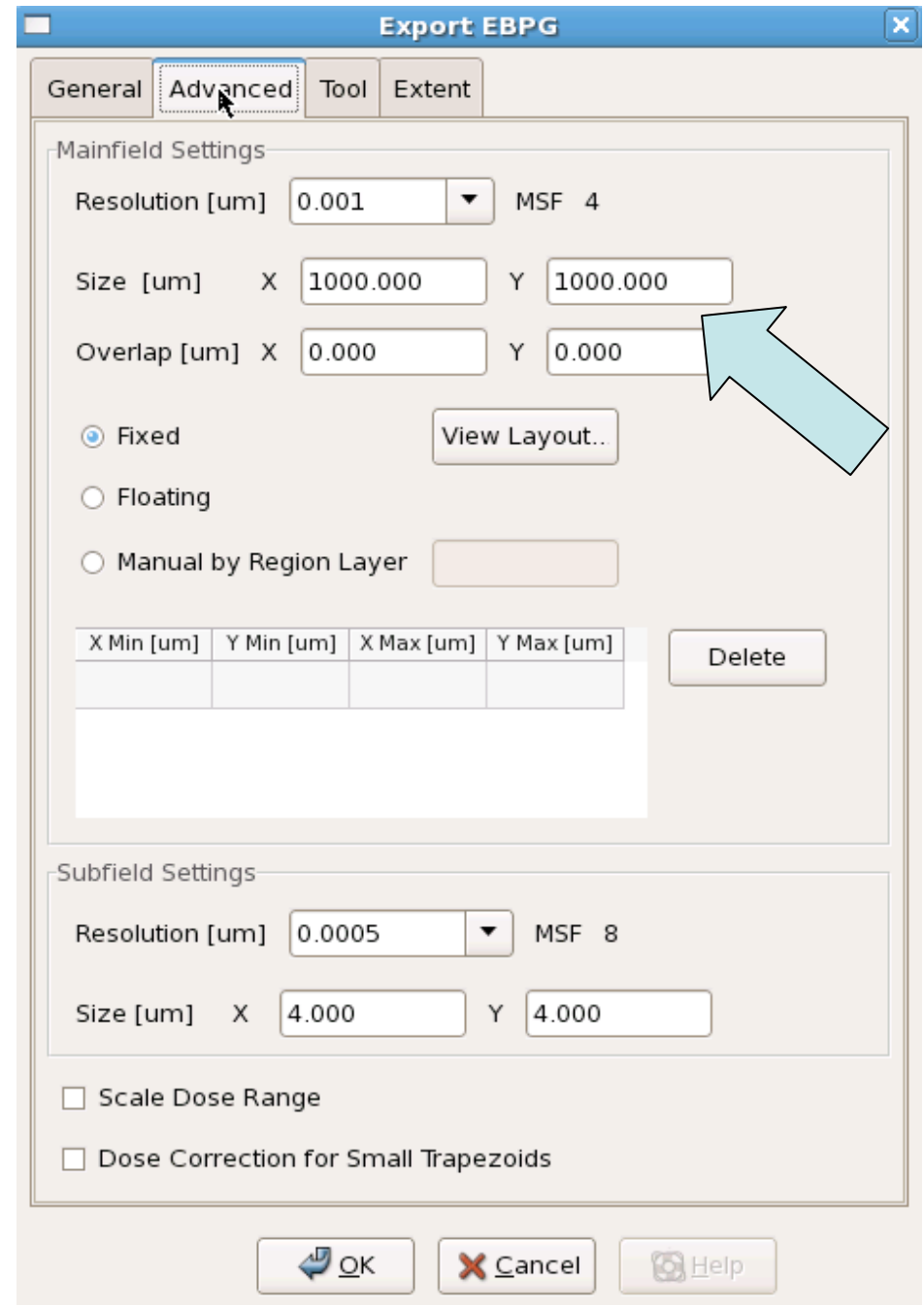
Here the term “resolution” means the EBPG’s bit size; that is, one DAC bit equals 1 nm. That’s the default, and you should not change it.

It’s unfortunate that Beamer uses the term “resolution” to mean two different things.

Now look at the “Mainfield Size”. This is a subset of the maximum exposure field  $(1 \text{ nm})(2^{20}) \approx 1 \text{ mm}$ . Some folks call this the “block size”, because the pattern will be chopped into blocks of this size.

The default size was  $600 \mu\text{m}$ , but Beamer changed it to  $1000 \mu\text{m}$  when you changed the step size. Why? Because it seemed like a good idea to someone, long ago.

Now you should change it to some sensible number, like...  $600 \mu\text{m}$ .



Make sure that the field (block) size is a multiple of the subfield size.

Otherwise, the left-over subfield will be written long after the others, leading to subfield misplacement due to drift.

Export EBPB

General **Advanced** Tool Extent

Mainfield Settings

Resolution [um] 0.001 MSF 4

Size [um] X 1000.000 Y 1000.000

Overlap [um] X 0.000 Y 0.000

Fixed  Floating  Manual by Region Layer

View Layout..

X Min [um]	Y Min [um]	X Max [um]	Y Max [um]

Delete

Subfield Settings

Resolution [um] 0.0005 MSF 8

Size [um] X 4.000 Y 4.000

Scale Dose Range

Dose Correction for Small Trapezoids

OK Cancel Help

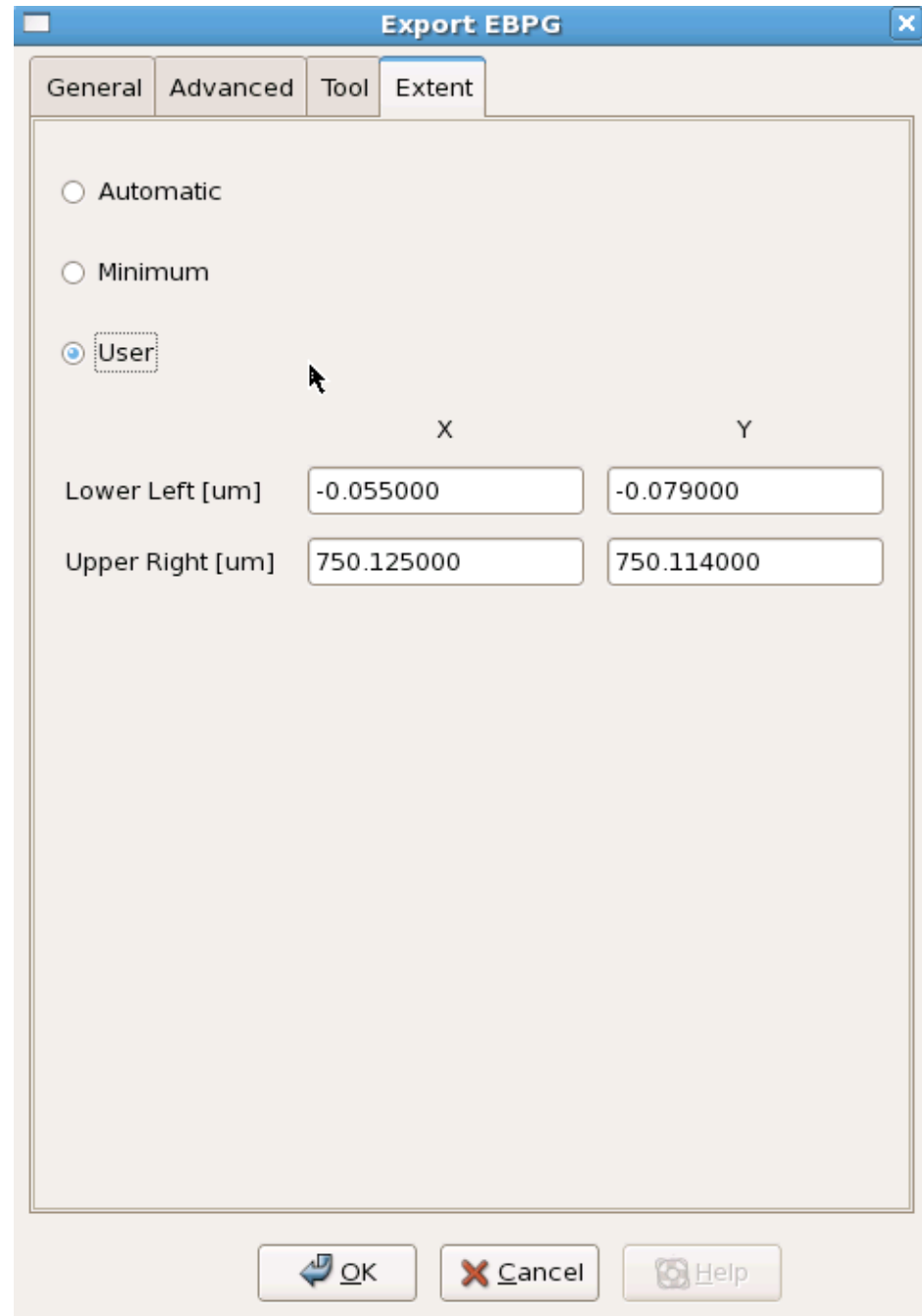
Thank goodness we can't change anything on the "tool" tab.



On the “extent” tab you may want to change the lower-left corner to control the field fracturing.

You should also pay attention to the upper-right corner, since the average of these coordinates will be the “chip center”.

The “chip center” will be the reference point for placement and alignment in Vistec’s exposure job software.

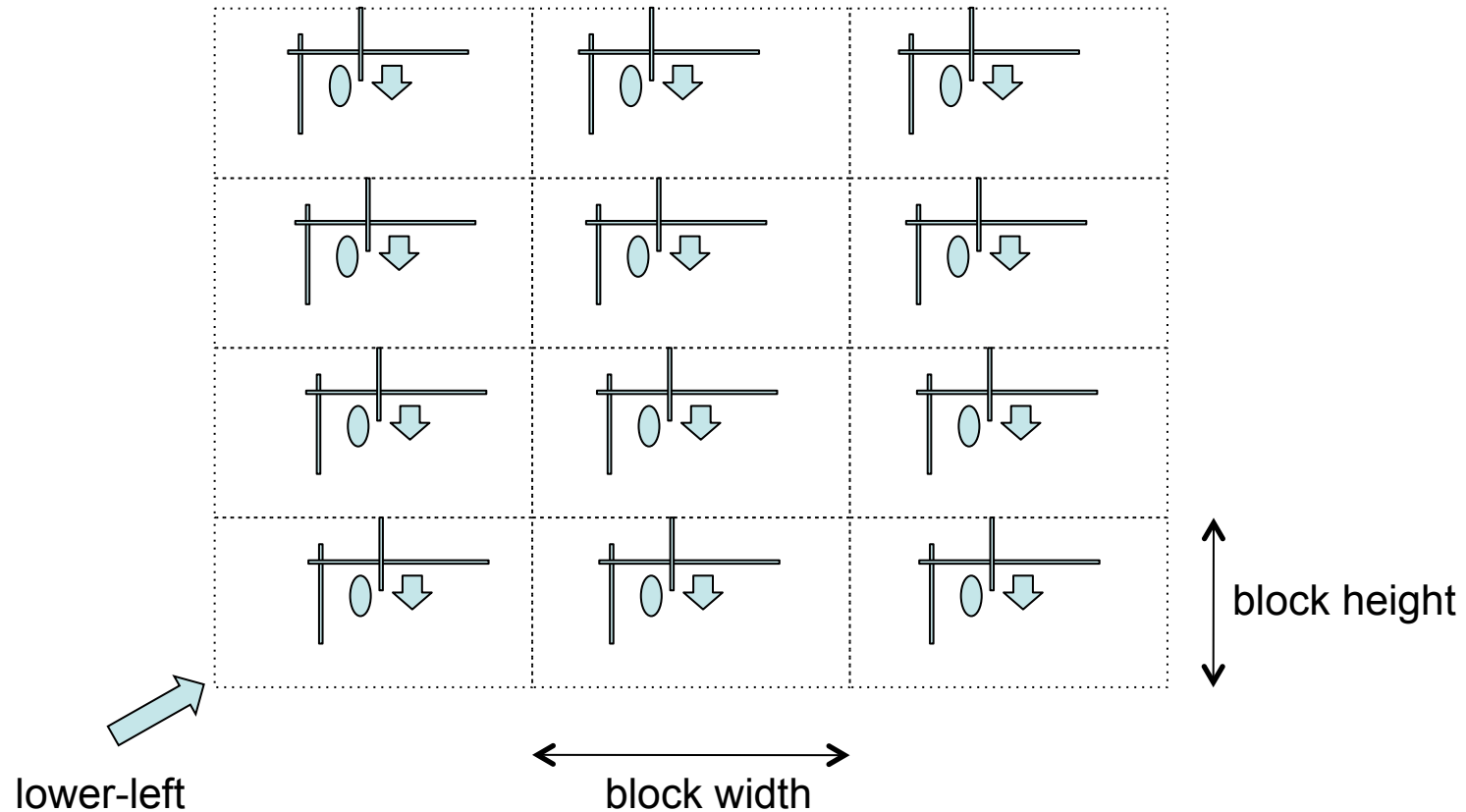




Click on the play button to start the fracturing process.  
When that is done, click on the same spot to see  
the fractured pattern



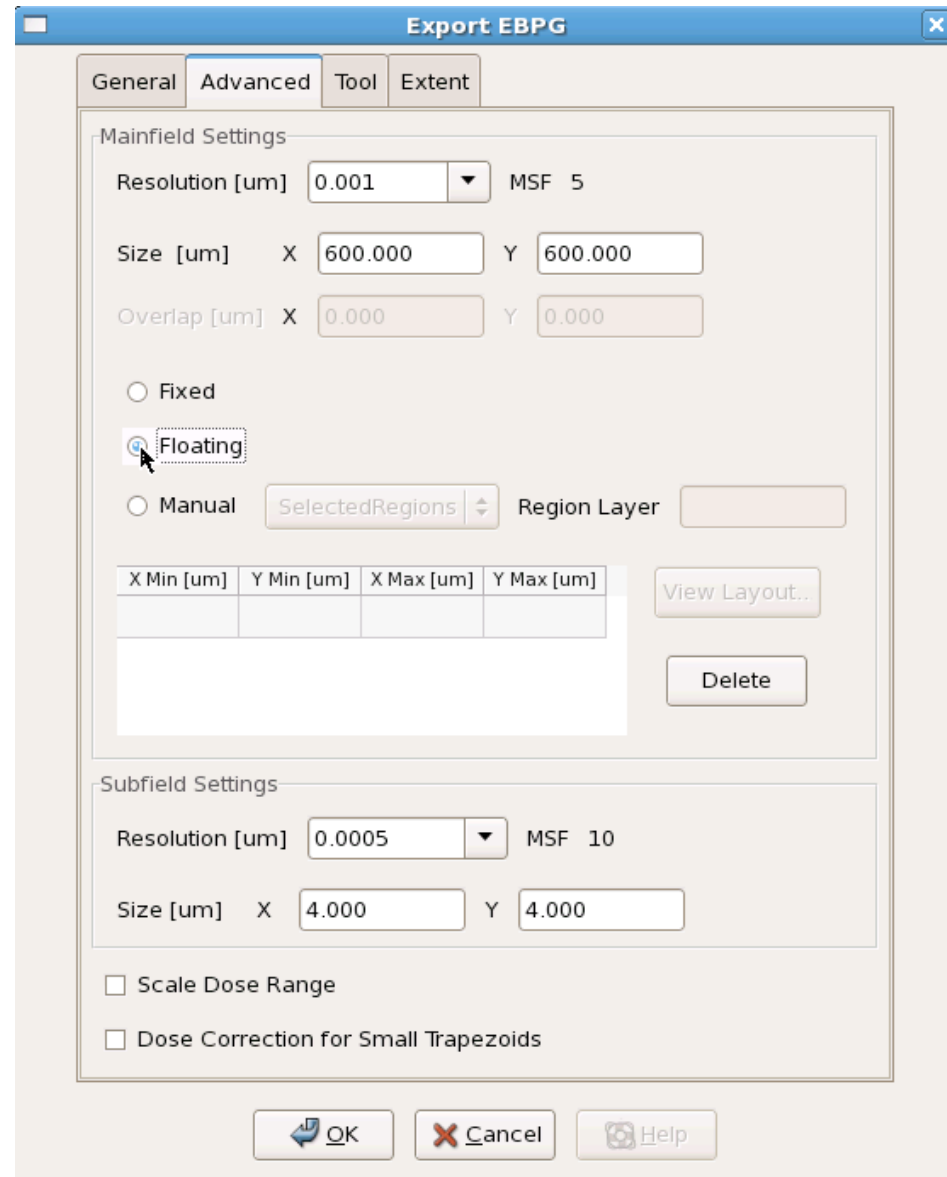
Choose the lower-left point and the block size so that stitching boundaries will avoid critical features. The sample stage will move at block boundaries, causing stitching errors of 15-20 nm.



Actually, you should think about field stitching while planning the design. You may have to go back to the CAD program and start over.

Alternatively, try using the “floating field” option, which will let Beamer attempt to center isolated features inside exposure fields.

For some designs this can be very handy.



Those are the three basic steps you always need:

Import

Extract

Export

But there are all sorts of other things you might need to do.

For example, suppose you need to crop the pattern.

You'll find that you cannot simply set the lower-left and upper-right corners in the "export" box. Instead, you'll need an extra "extract" step.



Layout Operation

Import Edit

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Extract

Grid

Heal NOT Bias

P-XOR Merge

OR AND MINUS

XOR

Import

Extract

Extract

Out GPF

Drag another "extract" over on top of the first. Then choose "Region Extraction".

Extract

Extract Extent

Layer / Sublayer

Layer(s) \*

Extraction Type

Cell Extraction

Cell Name --- entire layout ---

Region Extraction

X Min [um]	Y Min [um]	X Max [um]	Y Max [um]
450	450	550	550

Region Layer

Edit Layout... Delete Row

OK Cancel Help

Module Info Log Info

Mainfield Resolution Range min/max  
Maximum Mainfield Size (um): 1000  
Subfield Dac Bits: 14  
Maximum Subfield MSF: 512  
Subfield Resolution Range min/max  
Maximum Subfield Size (um): 4.000  
File type: VisTec GPF file

Import ./foo.gds  
File type: GDSII file  
Layerset: \*  
Single Path Import OFF  
Boxes Import OFF  
Zero Path Width 0.000000

Extract: not defined yet



click on “play” at the bottom  
to rerun the steps.

Then click there again to view  
the pattern.



Another important function is overlap removal, or “healing”. Actually, healing and overlap removal are two things, but in practice you always want to heal the shapes (merge them) after removing overlaps.

If you remove overlaps and heal the pattern, any information about layers and datatypes will be lost. So... healing is not allowed, if you need to assign doses.

How do you assign doses?

new flow - Layout BEAMER

File Edit View Help

Cut Copy Paste Up Save Run Run To Cancel Reset Viewer Detach

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Import Extract Extract FDA Out GPF

Module Info Log Info

Region Layer:  
Extent Mode: Keep Extent

Healing  
Target Layer: 1(0)  
Soft Frame [um]: 0.300000  
Hierarchical Processing: True

Processing Mode: Healing

Healing  
Target Layer: 1(0)  
Soft Frame [um]: 0.300000  
Hierarchical Processing: True

Processing Mode: Healing

Feature Dose Assignment

Assignment Dose Class Settings

Layer	rel. Dose

Assignment Type

Assign Value

Multiply Value

Import... Export...

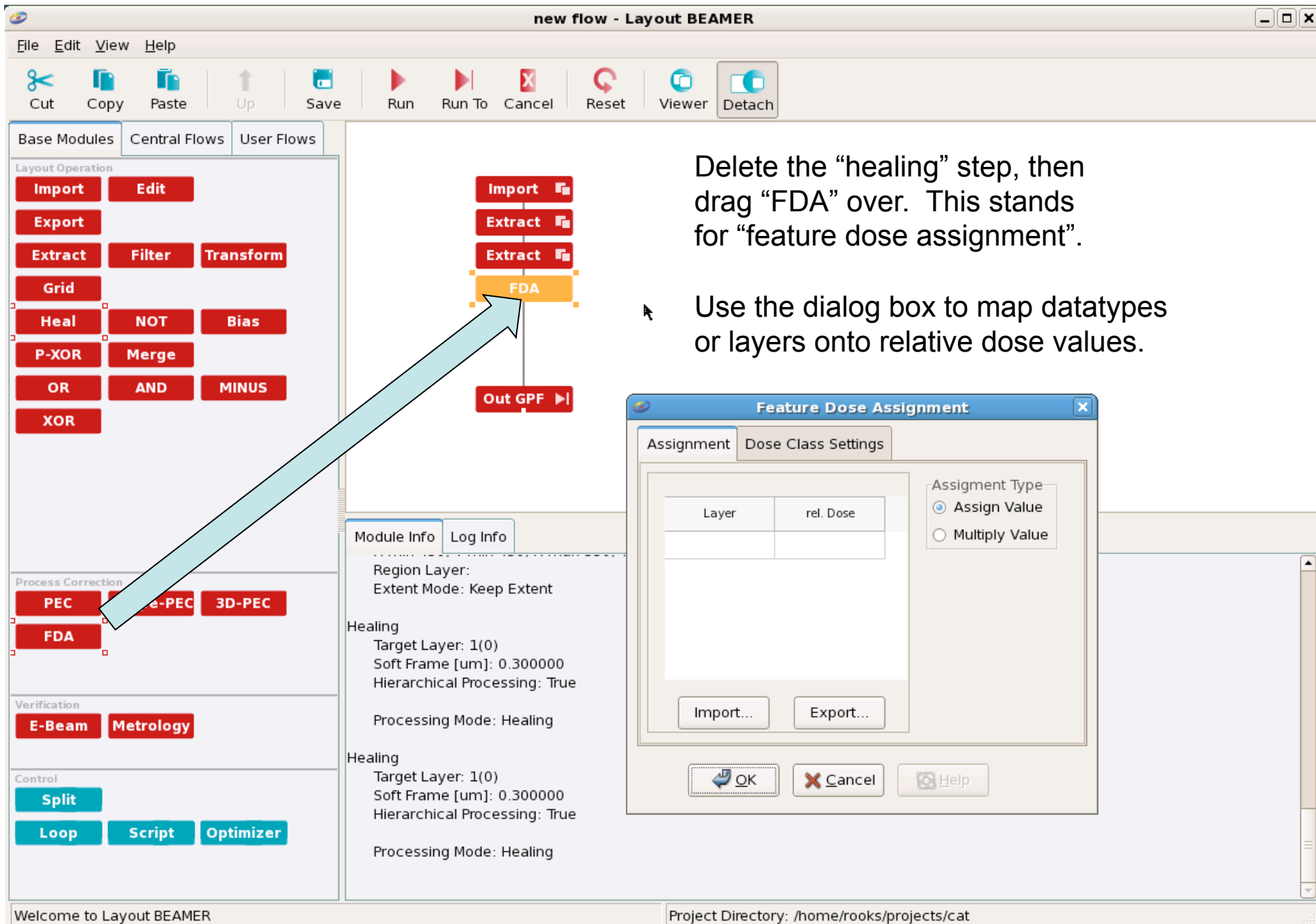
OK Cancel Help

Welcome to Layout BEAMER

Project Directory: /home/rooks/projects/cat

Delete the "healing" step, then drag "FDA" over. This stands for "feature dose assignment".

Use the dialog box to map datatypes or layers onto relative dose values.



When you pull down the list box under “layer”, you should see a list of all the layers and datatypes in your pattern.

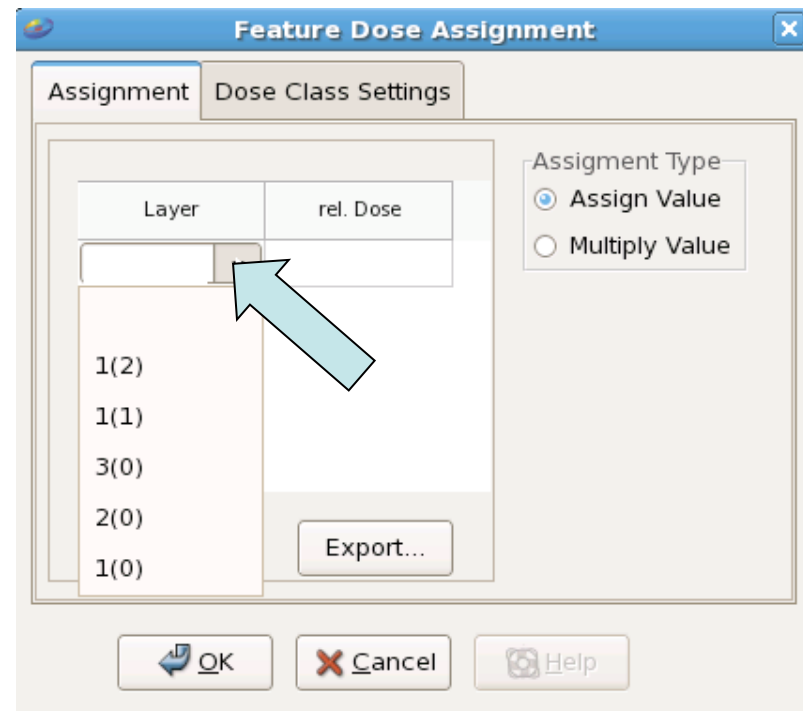
They are listed as

layer (datatype)

In this pattern, layer 0 includes shapes with datatypes 0, 1, 2.

The EBPG accepts RELATIVE dose values. Other e-beam writers let you create a dose variable that can be assigned at run-time. Not the EBPG.

(The “assignment type” choice seems to be irrelevant for the EBPG.)

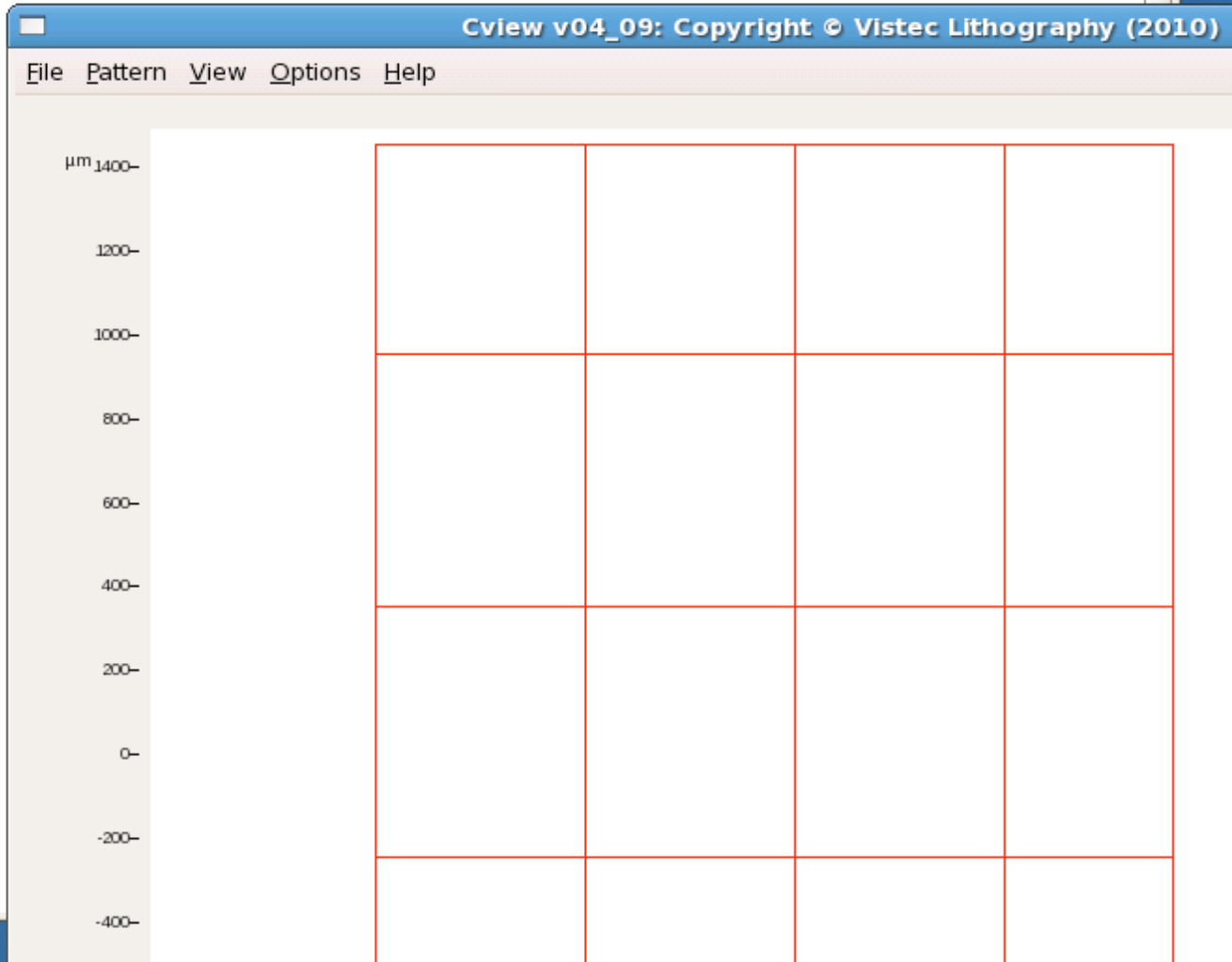


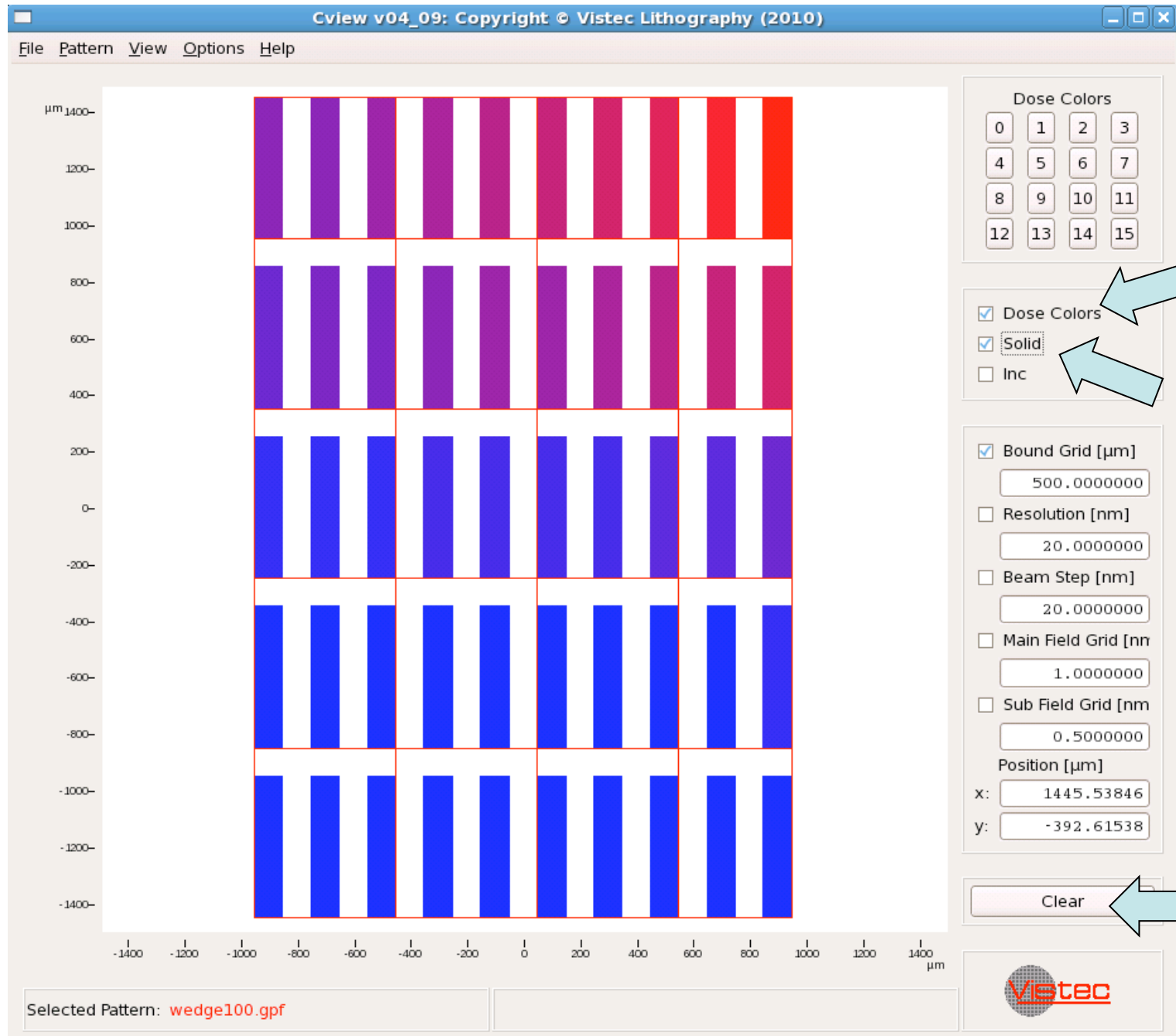


Checking the GPF file with Cview

```
rooks@lardnar:~/projects/cat
File Edit View Terminal Tabs Help

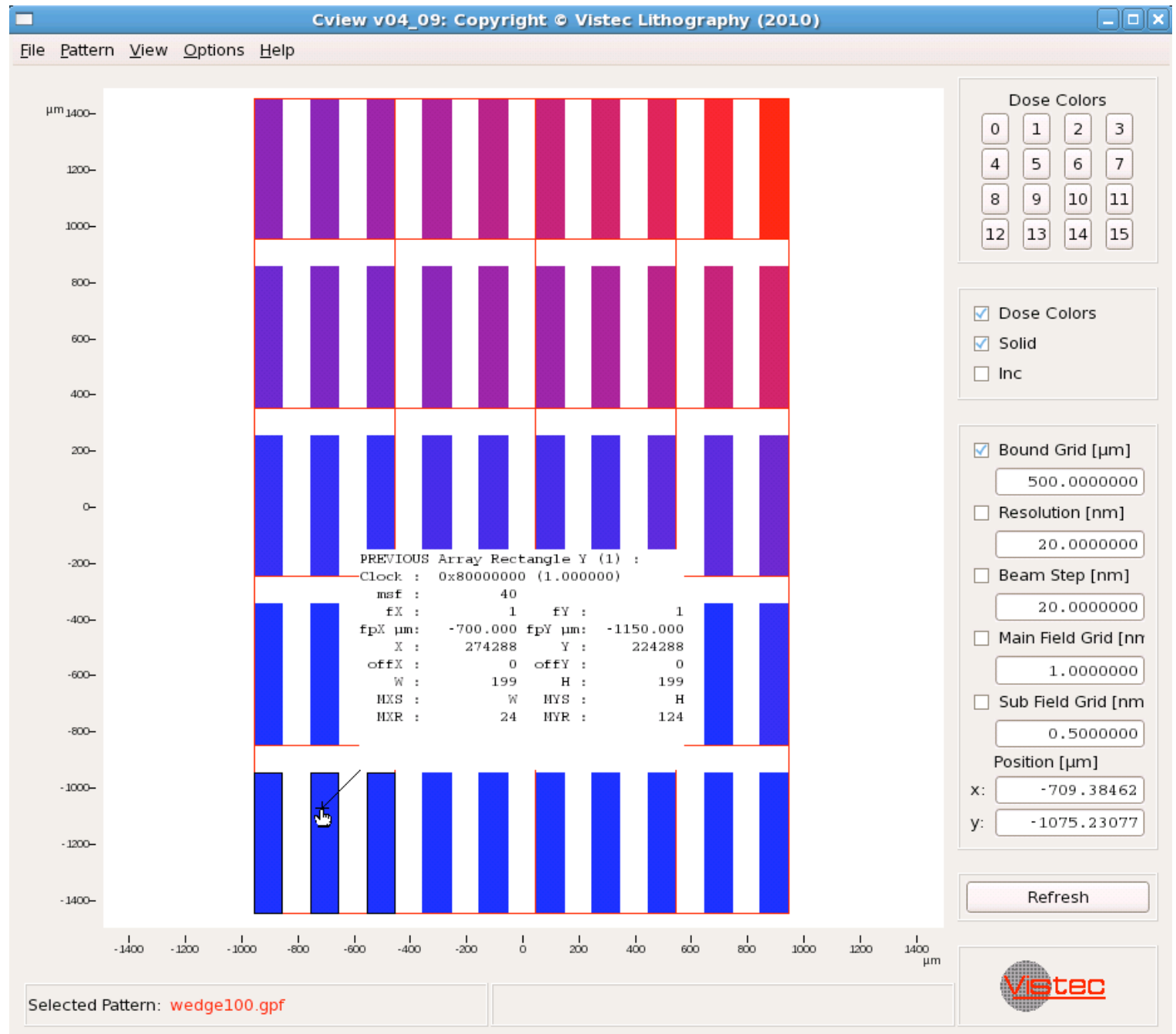
[rooks@lardnar cat]$
[rooks@lardnar cat]$ cview wedge100.gpf
█
```

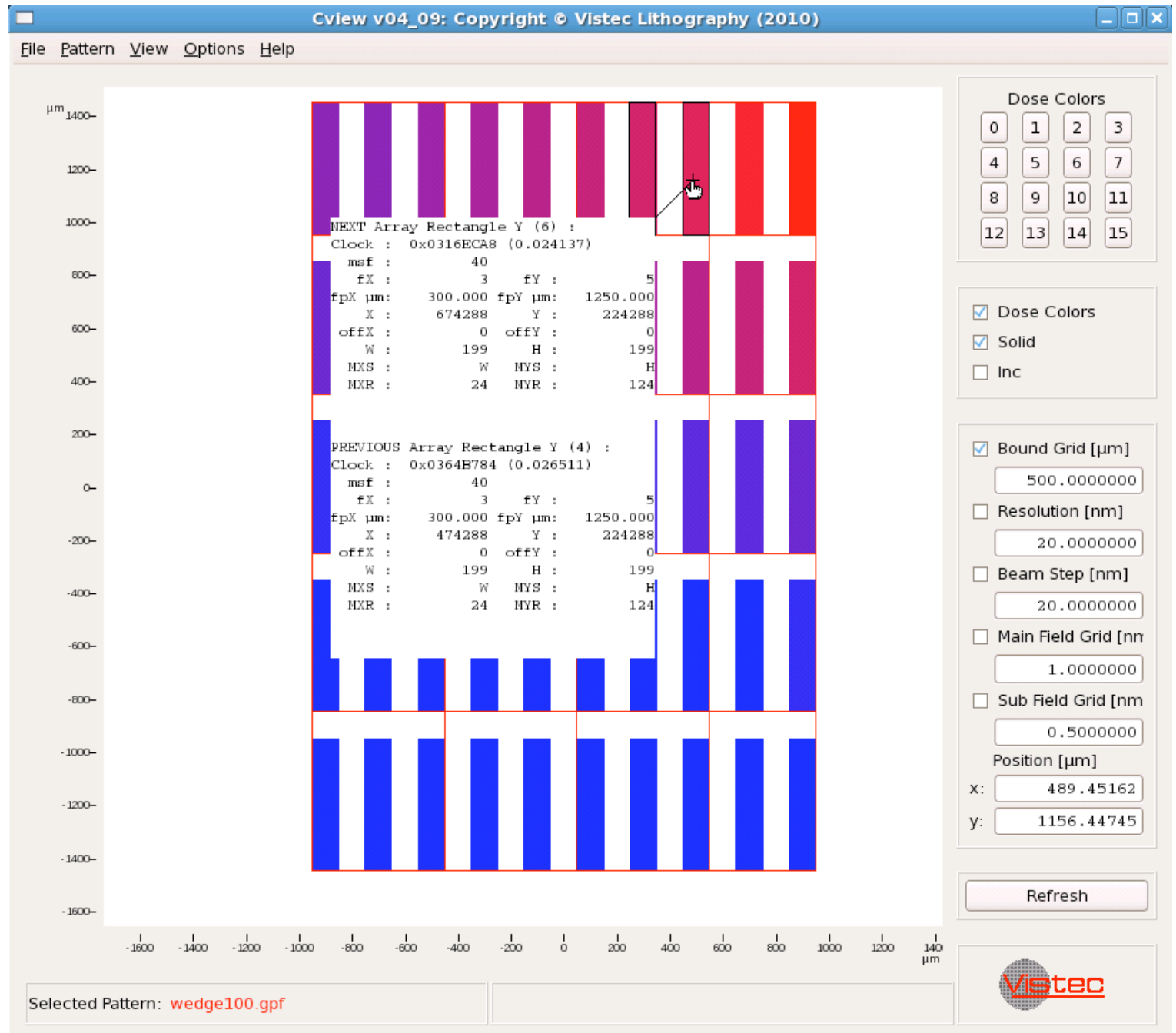




Same zooming action: UL to LR zooms in, LR to UL zooms out

Hover over a shape and press the Ctrl key to reveal details of a shape.





If you get a double report, that means there are overlapping shapes.

In this example, the overlap was intentional. In your pattern, maybe not.

Use  
pattern → header  
to reveal all  
the gory details.

Cvview v04\_09: Copyright © Vistec Lithography (2010)

File Pattern View Options Help

1 wedge100.gpf

Header... Ctrl+H

Statistics... Ctrl+S

wedge100.gpf

Generic Pattern Format, © Vistec Lithography

Version : 1.40

MainFieldResolution : 0.0010000, 0.0010000 [μm]

SubFieldResolution : 0.0005000, 0.0005000 [μm]

Resolution : 0.0200000, 0.0200000 [μm] 20, 20 [RC]

BeamStepSize : 0.0200000, 0.0200000 [μm] 40, 40 [RC]

PatternSize : 1900.0000000, 2900.0000000 [μm] 95000, 145000 [RC]

MainFieldSize : 500.0000000, 600.0000000 [μm] 25000, 30000 [RC]

SubFieldSize : 4.0000000, 4.0000000 [μm] 200, 200 [RC]

HighTension : 100 [kV] 100000000 [mV]

ShapeTypes : TRAPEZIUM 1

SubFieldPlacement : LOWERLEFT 2

NrMainFields : 20

MainFieldPlacement : MEANDER 2

FractureStyle : SUBFIELD | NONE 3

NrMainFieldBits : 20

NrSubFieldBits : 14

MaxMSF : 256

MinFreqFactor BIN : 0x28f5c28

MaxFreqFactor BIN : 0x80000000

NrFreqFactors : 50

PixelTime : 1.4e+11 (138083751144)

FileSize : 3144

HeaderOffset : 512

IndexOffset : 2504

MinStructureMemSize : 0

PatternName : wedge100

CreateDate : 0-10-2010

CreateTime : 11:14

ConverterName : Layout BEAMER

ConverterVersion : Layout ENGINE x64 Revision Number 4.00.004, Jul GDSII

SourceFormat : GDSII

Ok

Selected Pattern: wedge100.gpf

Vistec